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(71) Applicant: **CABOT MICROELECTRONICS CORPORATION** [US/US]; Legal Department, 870 North Commons Drive, Aurora, IL 60504 (US).

(72) Inventor: **PRASAD, Abaneshwar**; c/o Cabot Microelectronics Corporation, 870 North Commons Drive, Aurora, IL 60504 (US).

(74) Agents: **WESEMAN, Steven** et al.; Associate General Counsel, Intellectual Property, Cabot Microelectronics Corporation, 870 North Commons Drive, Aurora, IL 60504 (US).

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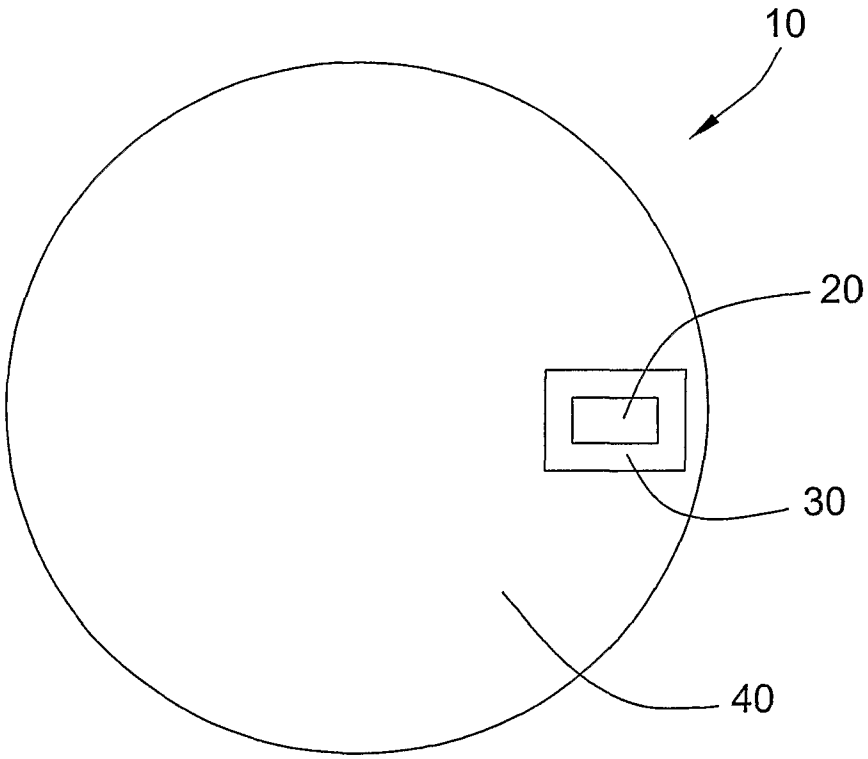
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— *as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii)) for all designations*

— *as to the applicant's entitlement to claim the priority of the earlier application (Rule 4.17(iii)) for all designations*

[Continued on next page]

(54) Title: POLISHING PAD COMPRISING HYDROPHOBIC REGION AND ENDPOINT DETECTION PORT



(57) Abstract: The invention provides a chemical-mechanical polishing pad comprising a polishing layer (10) comprising a hydrophobic region (30), a hydrophilic region (40), and an endpoint detection port (20). The hydrophobic region is substantially adjacent to the endpoint detection port (80). The hydrophobic region (30) comprises a polymeric material having a surface energy of 34 mN/rn or less and a polymeric material having a surface energy of more than 34 mN/m. The invention further provides a method of polishing a substrate comprising the use of the polishing pad.

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